

IN THE CLAIMS:

Please CANCEL claims 18, 19, 22, 27-30 and 33 without prejudice to or disclaimer of the recited subject matter.

Please AMEND claims 20, 23, 26 and 31, as follows. All 11 claims currently pending in this application are reproduced below, for the Examiner's convenience.

1-19. (Cancelled)

20. (Currently Amended) ~~A method according to claim 18;~~ An exposure method of exposing a substrate to a pattern, in which a mark in each of a plurality of layers on the substrate is detected for alignment of the substrate, said method comprising steps of:

illuminating a mark in each of a plurality of layers on a substrate;

detecting an image of the illuminated mark in each of the plurality of layers; and

setting an illumination condition in said illuminating step for the mark in each of the plurality of layers, wherein, in said setting step, the illumination condition is set based on a manual indication.

21. (Previously Presented) A method according to claim 20, wherein the manual indication is performed through a manual switching part.

22. (Cancelled)

23. (Currently Amended) ~~A method according to claim 18;~~ An exposure method of exposing a substrate to a pattern, in which a mark in each of a plurality of layers on the substrate is detected for alignment of the substrate, said method comprising steps of:

illuminating a mark in each of a plurality of layers on a substrate;

detecting an image of the illuminated mark in each of the plurality of layers; and

setting an illumination condition in said illuminating step for the mark in each of the plurality of layers,

wherein the illumination condition is set based on the detected image.

24. (Previously Presented) A method according to claim 23, wherein the image of the illuminated mark in each of the plurality of layers is detected in each of a plurality of illumination conditions, and the illumination condition is set for the mark in each of the plurality of layers based on the detected images.

25. (Previously Presented) A method according to claim 24, wherein the illumination condition is set for the mark in each of the plurality of layers based on a contrast of each of the detected images.

26. (Currently Amended) A method according to claim 24, wherein the setting is performed for each ~~lot of the substrate~~ of a plurality of substrates.

27-30. (Cancelled)

31. (Currently Amended) ~~An apparatus according to claim 29,~~ An exposure apparatus for exposing a substrate to a pattern, said apparatus detecting a mark in each of a plurality of layers on the substrate for alignment between the substrate and the pattern, said apparatus comprising:  
a detection system which illuminates a mark on the substrate and detects an image of the illuminated mark; and  
a setting system which sets an illumination condition of said detection system for a plurality of marks, used for alignment, on the substrate, with respect to each of the plurality of layers, wherein said setting system sets the illumination condition based on a manual indication.

32. (Previously Presented) An apparatus according to claim 31, wherein said setting system includes a manual switching part.

33. (Cancelled)